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	Application No.	Applicant(s)	
	Approación no.		
Notice of Allowability	10/633,552	KIKKAWA ET AL.  Art Unit	
Notice of Allowability	Examiner	Art Unit	
	Wayne Langel	1754	
The MAILING DATE of this communication appear All claims being allowable, PROSECUTION ON THE MERITS IS (herewith (or previously mailed), a Notice of Allowance (PTOL-85) of NOTICE OF ALLOWABILITY IS NOT A GRANT OF PATENT RICO of the Office or upon petition by the applicant. See 37 CFR 1.313	OR REMAINS) CLOSED in other appropriate comm GHTS. This application is	n this application.  If not included unication will be mailed in due course. <b>THIS</b>	
1. This communication is responsive to			
2. The allowed claim(s) is/are <u>1-6</u> .			
<ol> <li>Acknowledgment is made of a claim for foreign priority und</li> <li>a)    ☐ All b) ☐ Some* c) ☐ None of the:</li> </ol>		or (f).	
<ol> <li>Certified copies of the priority documents have</li> </ol>			
2.   Certified copies of the priority documents have			
<ol><li>Copies of the certified copies of the priority doc</li></ol>	uments have been receive	d in this national stage application from the	)
International Bureau (PCT Rule 17.2(a)).			
The Drawings filed 8/5/03 are Applicant has THREE MONTHS FROM THE "MAILING DATE" of noted below. Failure to timely comply will result in ABANDONMITHIS THREE-MONTH PERIOD IS NOT EXTENDABLE.	of this communication to file	e a reply complying with the requirements .	
4. A SUBSTITUTE OATH OR DECLARATION must be submit INFORMAL PATENT APPLICATION (PTO-152) which gives			
5. CORRECTED DRAWINGS (as "replacement sheets") must	be submitted.		
(a) ☐ including changes required by the Notice of Draftsperso	on's Patent Drawing Revie	w ( PTO-948) attached	
1) hereto or 2) to Paper No./Mail Date			
(b) including changes required by the attached Examiner's Paper No./Mail Date	Amendment / Comment of	r in the Office action of	
Identifying indicia such as the application number (see 37 CFR 1.8 each sheet. Replacement sheet(s) should be labeled as such in the	84(c)) should be written on the header according to 37 C	the drawings in the front (not the back) of FR 1.121(d).	
6. DEPOSIT OF and/or INFORMATION about the depose attached Examiner's comment regarding REQUIREMENT F	it of BIOLOGICAL MAT	ERIAL must be submitted. Note the	
Attachment(s)	E   Nation of the	oformal Patent Application (DTO 152)	
<ol> <li>Notice of References Cited (PTO-892)</li> <li>Notice of Draftperson's Patent Drawing Review (PTO-948)</li> </ol>	<del>-</del>	nformal Patent Application (PTO-152) Summary (PTO-413),	
	Paper No	/Mail Date	
<ol> <li>Information Disclosure Statements (PTO-1449 or PTO/SB/08         Paper No./Mail Date     </li> </ol>	<i>,,</i> –	Amendment/Comment	
<ol> <li>Examiner's Comment Regarding Requirement for Deposit of Biological Material</li> </ol>	8. 🛛 Examiner's	Statement of Reasons for Allowance	
or biological material	9. 🗌 Other	<u>_</u> .	

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The following is an examiner's statement of reasons for allowance: Appplicants admit that the inner surface polishing process is applied frequently for preventing adsorption of water or impurity gases to the inner surface of a high pressure vessel and keeping the high purity of the filled gas. (See pages 1-3 of applicants' specification.) However applicants do not admit that it is known to polish the inner surface of a high pressure gas container mainly made of iron, which has had a pressure test by hydraulic pressure, by 5 to 100 microns thickness on average such that the value of dividing the area of the Si2s peak by the area of the Fe2p3 peak in the X-ray photoelectron spectrum of the container inner surface is 0.3 or less, as required by claims 1, 2, 5 and 6. Nor is there any teaching, disclosure, suggestion, or motivation in the prior art to do so. Applicants' specification discloses in the paragraph bridging pages 3 and 4 that the impurity causing the purity decline in the halogen containing gas is a silicon halide produced by the reaction of the residual Si content on the container inner surface with the filled gas, and the production of the silicon halide can be restrained by reducing the Si residual amount in the container inner surface top layer part quantitatively determined by X-ray photoelectron spectroscopy to a certain level or less so that the purity decline of the halogen containing gas can be prevented. Accordingly claims 3 and 4 are also allowable, since they require that the halogen containing gas be filled in a high pressure gas container process by polishing the inner surface of a high pressure gas container mainly made of iron, which has had a pressure test by hydraulic pressure, by 5 to 100 microns thickness on average such that the value of dividing the area of the Si2s peak by the area of the Fe2p, peak in the X-ray photoelectron spectrum of the container inner

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surface is 0.3 or less. Although halogen containing gases filled in high pressure gas containers are well-known (see col. 2, lines 11-36 of Bealky et al (US 5,928,743) and col. 1, lines 11-44 of Zdunek et al (US 6,290,088), for example), the halogen containing gas filled in the high pressure container recited in claims 3 and 4 would not be obvious thereover since the container would be different in that the recited polishing step would restrain the production of silicon halide so that the purity decline of the halogen containing gas can be prevented, as discussed earlier.

Any comments considered necessary by applicant must be submitted no later than the payment of the issue fee and, to avoid processing delays, should preferably accompany the issue fee. Such submissions should be clearly labeled "Comments on Statement of Reasons for Allowance."

Any inquiry concerning this communication or earlier communications from the examiner should be directed to Wayne Langel whose telephone number is 571-272-1353. The examiner can normally be reached on Mondays to Fridays from 8 to 3:30.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Stanley Silverman, can be reached on 571-272-1358. The fax phone number for the organization where this application or proceeding is assigned is 571-273-8300.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR.

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Business Center (EBC) at 866-217-9197 (toll-free).

Wayne Langel

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Primary Examiner

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